

Title (en)

Method and apparatus for manufacturing electron source, and method of manufacturing image forming apparatus

Title (de)

Verfahren und Vorrichtung zur Herstellung einer Elektronenquelle und eines Bilderzeugungsgerät

Title (fr)

Procédé et appareil pour la fabrication d'une source d'électrons et d'un dispositif de formation d'images

Publication

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Application

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- JP 5165299 A 19990226
- JP 14981099 A 19990528

Abstract (en)

[origin: EP0964421A1] This invention discloses an electron source manufacturing method including the step of applying a voltage to a plurality of conductive members by applying a potential to first portions of the plurality of conductive members serving as at least part of electron-emitting devices via a wiring commonly connected to the plurality of conductive members, and applying a potential to second portions of the plurality of conductive members, wherein the potential applied to the second portions of the plurality of conductive members is set to relax the difference in voltage applied to the plurality of conductive members owing to the difference between potentials at portions respectively connected to the first portions of the plurality of conductive members in the wiring commonly connected to the plurality of conductive members. This method may be included in the manufacture of an image forming apparatus including such an electron source. Also disclosed is apparatus including circuits for performing this method. <IMAGE>

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